IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Sylvia H. Pas

Examiner: TBD

Serial No:

TBD

Art Unit: TBD

Filed:

01/11/01

Docket No.: TI-22398

For:

SYSTEM AND METHOD FOR INTEGRATED OXIDE REMOVAL AND

PROCESSING OF A SEMICONDUCTOR WAFER

PRELIMINARY AMENDMENT

January 11, 2001

Assistant Commissioner for Patents

Washington, DC 20231

Dear Sir:

Please amend the above referenced application as follows:

In the Specification:

Page 1, before line 1, insert -- This application claims priority under 35 USC §

119(e)(1) of provisional application numbers 60/178,647 filed 01/28/00.F-

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